	Hits	Search Text	DBs
23	70	((heat$4 or anneal$7 or bak$4 or cur$4) same (pattern or mask) same (trench$4 or hole) same ((liquid or solution) near26 (metal$4 or pattern or hydrophobic$4 or polymer$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer$3 or photosenstive or radiation$6sensitive)) and ((trench$3 or hole or contact$6hole or via or (aspect$8 near6 ratio)) same (fill$4 or (conformal$4 near9 (fill$4 or deposit$4 or layer$4))) same (plural$4 or multiple$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	37	S26 and (develop$4 or strip$4 or remov$4) and ((remov$4 or eliminat$4 or strip$4) same (liquid or deposit$4 or solution or hydrophobic or polymer$4 or metal$3) same ((pattern or mask) near16 (portion or region or area)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	75	((heat$4 or anneal$7 or bak$4 or cur$4) same (pattern or mask) same (trench$4 or hole) same ((liquid or solution) near26 (metal$4 or pattern or hydrophobic$4 or polymer$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer$3 or photosenstive or radiation$6sensitive)) and ((trench$3 or hole or contact$6hole or via or (aspect$8 near6 ratio)) same (fill$4 or immers$4 or (conformal$4 near9 (fill$4 or deposit$4 or layer$4))) same (plural$4 or multiple$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	37	S28 Not S27	US-PGPUB; USPAT
27	38	S28 NOT S27	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	206	((heat$4 or anneal$7 or bak$4 or cur$4 or post$5heat$4 or thermal$4 or solidifying or solidification or solidify) same (pattern or mask) same (trench$4 or hole or opening or via) same ((liquid or solution or immers$4) near26 (metal$4 or pattern or hydrophobic$4 or polymer$3 or inorganic or organic))) and ((mask or pattern) near16 (photoresist or resist or polymer$3 or photosenstive or radiation$6sensitive)) and ((trench$3 or hole or contact$6hole or via or (aspect$8 near6 ratio) or opening) same (fill$4 or dip$4 or immers$4 or (conformal$4 near9 (fill$4 or deposit$4 or layer$4))) same (plural$4 or multiple$4 or several))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	131	S31 NOT S28	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB